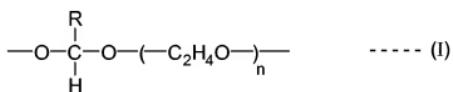


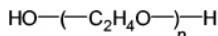
Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (currently amended) A chemically amplified photosensitive resin composition comprising (A) an alkali-soluble novolak resin, (B) a resin or compound which in itself is insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid, (C) an acid generating agent, and (D) a photosensitizing agent containing a quinonediazide group, and (E) an alkali-soluble acrylic resin, wherein said resin or compound which is itself insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid has a structural unit represented by the general formula (I):



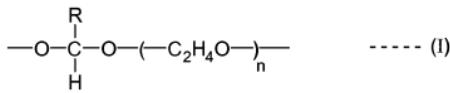
wherein R represents a saturated alkyl group having 3 to 10 carbon atoms and n is an integer from 1 to 10, said structural unit represented by the general formula (I) obtained by reacting RCHO, RCH(OH)₂, or RCH(OR¹)₂, wherein R is defined above, and R¹ represents an alkyl group, with



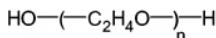
wherein n is defined above, and wherein said alkali-soluble acrylic resin contains a structural unit derived from a (meth)acrylic acid, a structural unit derived from an alkylmethacrylate and, as required, a structural unit derived from styrene.

Claims 2. to 4. (canceled)

5. (currently amended) A chemically amplified photosensitive resin composition according to Claim 3 A chemically amplified photosensitive resin composition comprising (A) an alkali-soluble novolak resin, (B) a resin or compound which in itself is insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid, (C) an acid generating agent, (D) a photosensitizing agent containing a quinonediazide group, and (E) an alkali-soluble acrylic resin, wherein said resin or compound which is itself insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid has a structural unit represented by the general formula (I):



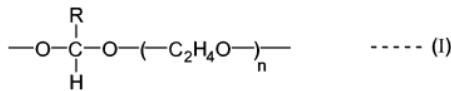
wherein R represents a saturated alkyl group having 3 to 10 carbon atoms and n is an integer from 1 to 10, said structural unit represented by the general formula (I) obtained by reacting RCHO, RCH(OH)₂, or RCH(OR¹)₂, wherein R is defined above, and R¹ represents an alkyl group, with



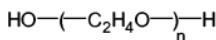
wherein n is defined above, wherein said alkali-soluble acrylic resin contains a structural unit derived from a hydroxyalkylmethacrylate, a structural unit derived from an alkylmethacrylate and, as required, a structural unit derived from styrene.

6. (currently amended) A chemically amplified photosensitive resin composition according to Claim 1, which further comprises A chemically amplified photosensitive resin

composition comprising (A) an alkali-soluble novolak resin, (B) a resin or compound which in itself is insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid, (C) an acid generating agent, (D) a photosensitizing agent containing a quinonediazide group, and (F) a compound containing at least two vinyloxyalkylester groups, wherein said resin or compound which is itself insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid has a structural unit represented by the general formula (I):



wherein R represents a saturated alkyl group having 3 to 10 carbon atoms and n is an integer from 1 to 10, said structural unit represented by the general formula (I) obtained by reacting RCHO, RCH(OH)₂, or RCH(OR¹)₂, wherein R is defined above, and R¹ represents an alkyl group, with

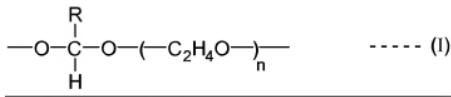


wherein n is defined above.

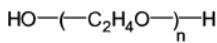
Claims 7. to 12. (canceled)

13. (previously presented) A chemically amplified photosensitive resin composition according to Claim 3, which further comprises comprising (A) an alkali-soluble novolak resin, (B) a resin or compound which in itself is insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid, (C) an acid generating agent, (D) a photosensitizing agent containing a quinonediazide group, (E) an alkali-soluble acrylic

resin, and (F) a compound containing at least two vinyloxyalkylester groups, wherein said resin or compound which is itself insoluble or slightly soluble in alkali, but becomes soluble in alkali by the action of an acid has a structural unit represented by the general formula (I):



wherein R represents a saturated alkyl group having 3 to 10 carbon atoms and n is an integer from 1 to 10, said structural unit represented by the general formula (I) obtained by reacting RCHO, RCH(OH)₂, or RCH(OR¹)₂, wherein R is defined above, and R¹ represents an alkyl group, with



wherein n is defined above.

14. (currently amended) A chemically amplified photosensitive resin composition according to Claim [[4]] 1, which further comprises (F) a compound containing at least two vinyloxyalkylester groups.

15. (previously presented) A chemically amplified photosensitive resin composition according to Claim 5, which further comprises (F) a compound containing at least two vinyloxyalkylester groups.

Claims 16. and 17. (canceled)

18. (currently amended) A chemically amplified photosensitive resin composition according to Claim [[4]] 1, wherein the ratio by weight of said components (A) : (B) : (C) : (D) : (E) : (F) is 100 : 1 to 50 : 0.02 to 10 : 1 to 30 : 0 to 200 : 0 to 30.

19. (previously presented) A chemically amplified photosensitive resin composition according to Claim 5, wherein the ratio by weight of said components (A) : (B) : (C) : (D) : (E) : (F) is 100 : 1 to 50 : 0.02 to 10 : 1 to 30 : 0 to 200 : 0 to 30.

20. (previously presented) A chemically amplified photosensitive resin composition according to Claim 6, wherein the ratio by weight of said components (A) : (B) : (C) : (D) : (E) : (F) is 100 : 1 to 50 : 0.02 to 10 : 1 to 30 : 0 to 200 : 0 to 30.